

POSITIONING STAGE WITH STATIONARY AND MOVABLE MAGNET TRACKS

ABSTRACT OF THE DISCLOSURE

5 A stage positioning system including a stationary frame, a slide movable relative to the frame in a first direction, and a support platform connected to the slide and movable therewith in the first direction. The support platform is movably attached to the slide for movement in a second direction generally orthogonal to the first direction. The system will further include a first linear motor containing a first magnet assembly and a first coil device that engages the first magnet assembly to move the slide in the first direction. A second linear will contain a second magnet assembly and a second coil device that engages the second magnet assembly to move the support platform in the second direction. The stage positioning system is particularly suited for positioning an article in electron beam or EUV light
10 lithography systems.

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